

PATENT

Atty. Dkt. No. AMAT/4213.P1/MASK/MASK-ETCH/ARNOLD S

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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JUN 17 2004

In re Application of:
Buie, et al.

Serial No.: 10/024,958

Confirmation No.: 3439

Filed: December 18, 2001

For: Etch Process Photolithographic
Reticle Manufacturing with
Improved Etch Bias

Group Art Unit: 1765

OFFICIAL

Examiner: Kin-Chan Chen

MAIL STOP AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

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I hereby certify that this correspondence and the documents referred to as attached therein are being facsimile transmitted to the U.S. Patent and Trademark Office to the fax number indicated by the Examiner, namely, fax number 703-872-9306 to the attention of the named Examiner, on the date below.

6/17/04
Date

Kin-Chan Chen
Signature

Dear Sir:

RESPONSE TO FINAL OFFICE ACTION DATED MARCH 18, 2004

In response to the Final Office Action dated March 18, 2004, having a shortened statutory period for response set to expire on June 18, 2004, please enter this response and reconsider the claims pending in the application for reasons discussed below. Although Applicant believes that no additional fees are due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/4213.P1/KMT, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper. Remarks begin on page 7 of this paper.

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COMPANY: USPTO
FROM: Brian K. Hrna
PAGE(S) with cover: 11
ORIGINAL TO FOLLOW? ☐ YES ☒ NO

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RESPONSE TO FINAL OFFICE ACTION DATED MARCH 18, 2004

TITLE: Etch Process Photolithographic Reticle Manufacturing with Improved Etch Bias
U.S. SERIAL NO.: 10/024,958
FILING DATE: December 18, 2001
INVENTOR: Buie, et al.
EXAMINER: Kin-Chan Chen
GROUP ART UNIT: 1765
CONFIRMATION NO.: 3439

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